

- 1           1.    A method comprising:  
2                   forming a photoresist from a branched chain  
3   scission polymer.
- 1           2.    The method of claim 1 including providing  
2   scissionable linkages and nonscissionable linkages in said  
3   polymer.
- 1           3.    The method of claim 1 including providing a  
2   scionable linkage in a branch of said polymer.
- 1           4.    The method of claim 1 including forming a  
2   photoresist including a polymer having a molecular weight  
3   greater than 10,000 Daltons.
- 1           5.    The method of claim 1 including forming a  
2   photoresist including a polymer having a branch having a  
3   molecular weight greater than 5000 Daltons.
- 1           6.    The method of claim 1 including forming a polymer  
2   including oligo-4-hydroxystyrene.
- 1           7.    The method of claim 6 including forming tertiary  
2   carbonated linked branches.

1           8.    The method of claim 6 including forming an oligo-  
2   1,4-dihydroxyphenylcarbonate-bis tertiary alcohol.

1           9.    The method of claim 8 including appending a  
2   tertiary alcohol carbonate side chain on said polymer.